

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
1	BRS	L1	329	((thin adj film adj stack) or film) near8 MEMS	USPA T; US-P GPUB ; EPO; JPO; DERW ENT	2004/04/1 1 11:10	
2	BRS	L2	1997	359/290-298.CCLS.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT	2004/04/1 1 11:11	
3	BRS	L3	16	1 AND 2	USPA T; US-P GPUB ; EPO; JPO; DERW ENT	2004/04/1 1 11:11	
4	BRS	L4	2697	430/319,320,321.CCLS.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT	2004/04/1 1 11:11	
5	BRS	L5	3	1 AND 4	USPA T; US-P GPUB ; EPO; JPO; DERW ENT	2004/04/1 1 11:12	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
6	BRS	L8	31890	427/162-248.1.CCLS.	USPA T; US-P GPUB ; EPO; JPO; DERW ENT	2004/04/1 1 11:26	
7	BRS	L9	3	1 AND 8	USPA T; US-P GPUB ; EPO; JPO; DERW ENT	2004/04/1 1 11:26	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
1	BRS	L1	10285	((microelectromechanical adj system ) or MEMS)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/17 09:18	
2	BRS	L2	132063	etch\$ and pattern\$3 and deposit\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/17 09:20	
3	BRS	L3	3273	1 and 2	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/17 09:21	
4	BRS	L4	5	3 and (metal) and (conductive adj oxide or oxide ) and (fluoride) and (silicide) and (polymer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/17 09:38	
5	BRS	L5	816	216/2.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/17 09:38	

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
6	BRS	L6	1	4 and 5	USPAT; US-P GPUB ; EPO; JPO; DERW ENT	2004/04/17 09:38	